CORRECTION TO THE PAPER
"SILVER-NANOPARTICLE-BASED ETCH MASK CONTROL FOR SUBWAVELENGTH STRUCTURE DEVELOPMENT"

Nazme Moushuny¹, Kamal Alameh¹², V. Rajendran³, Yong Tak Lee²

¹Electron Science Research Institute, Edith Cowan University, 270 Joondalup Dr, Joondalup, WA 6027, Australia
²Department of Nanobio Materials and Electronics, Gwangju Institute of Science and Technology, World-Class University (WCU), Gwangju Institute of Science & Technology (GIST), Gwangju 500–712, South Korea
³Centre for Nano Science and Technology, K S R College of Technology, K S R Kalvi Nagar, Tiruchengode — 637 215, Namakkal (Dt.), Tamil Nadu, India

PACS 61.46.df

In the text published in Nanosystems: Physics, Chemistry, Mathematics, 4(3) (2013), P. 387–394, figure 6 should be replaced by the following more precise figure.
Fig. 6. Reflection spectra for various SWG structures developed using 10 nm, 8 nm and 5 nm thick Ag films on Si and GaAs substrates, annealed at different temperatures.